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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
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10/629,337

07/28/2003

John McCollum

ACT-368

6310

28661

7590

11/21/2005

EXAMINER

SOWARD, IDA M

SIERRA PATENT GROUP, LTD.

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STATELINE, NV 89449

ART UNIT

PAPER NUMBER

2822

DATE MAILED: 11/21/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

DETAILED ACTION

This Office Action is in response to the amendment filed October 7, 2005.

Response to Amendment

Applicant's request for reconsideration of the finality of the rejection of the last Office action is persuasive and, therefore, the finality of that action is withdrawn.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 8-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Williams et al. (5,726,477).

In regard to claim 8, Williams et al. teach a transistor 420 for an integrated circuit comprising: a p-type substrate 402; an n-type region disposed 421 over said p-type substrate 402; n-type buried layers 423A & 423B disposed at about a boundary between said substrate 402 and said n-type region 421, said buried layers 423A & 423B doped to a higher level than said n-type region 421; spaced apart p-type source and drain regions 426 & 428 disposed in said n-type region 421 forming a channel therein; a control gate 424 disposed above and insulated from said channel; and said substrate

Art Unit: 2822

and said n-type region each are biased (Figure 12, columns 9-10, lines 1-67 and 1-1-59, respectively).

In regard to claim 9, Williams et al. teach an isolation trench 406 & 408 disposed in the n-type region 421 and surrounding the source and drain regions 426 & 428, the isolation trench 408 & 408 extending down into the substrate 402 (Figure 12, columns 9-10, lines 1-67 and 1-1-59, respectively).

However, Williams et al. fail to teach said substrate and said n-type region and said n-type buried layers each biased such that said n-type region is fully depleted.

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to also bias the n-type buried layers of the transistor structure as taught by Williams et al. so that the n-type region is fully depleted to create threshold adjustable transistors (column 2, lines 50-55).

Claims 26-27 are rejected under 35 U.S.C. 103(a) as being unpatentable over Williams et al. (5,726,477) as applied to claims 8-9 above, and further in view of Uchida (US 2002/0031882 A1).

Williams et al. teach all mentioned in the rejection above.

However, Williams et al. fail to teach the various regions and layers having the opposite conductivity type.

In regard to claim 26, Uchida teaches a transistor for an integrated circuit comprising: an n-type substrate 1; a p-type region 14 disposed over said n-type substrate 1; p-type buried layer 17 disposed at about a boundary between said

substrate 1 and said p-type region 14; spaced apart n-type source and drain regions disposed in said p-type region 14 forming a channel therein; a control gate 27 disposed above and insulated from said channel (Figure 5, pages 4-5, paragraphs [0053]-[0064]).

In regard to claim 27, Uchida teaches an isolation trench 2 disposed in the p-type region 14 and surrounding the source and drain regions (Figure 5, pages 4-5, paragraphs [0053]-[0064]).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to also bias the n-type buried layers of the transistor structure as taught by Williams et al. with the transistor structure having opposing conductivity type of the regions and layers as taught by Uchida to reduce power consumption (page 1, paragraph [0004]).

Claims 17-18 and 35-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Williams et al. (5,726,477) and Uchida (US 2002/0031882 A1) as applied to claims 8-9 and 26-27 above, and further in view of Taniguchi et al. (US 6,617,632 B2).

Williams et al. and Uchida teach all mentioned in the rejection above.

However, Williams et al. and Uchida fail to teach a floating gate.

Taniguchi et al. teach a floating gate 4 (Figure 6, column 12, lines 12-23).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to also bias the n-type buried layers of the transistor structure as taught by Williams et al. and the transistor structure having opposing

Art Unit: 2822

conductivity type of the regions and layers as taught by Uchida with the transistor having a floating gate as taught by Taniguchi et al. to provide a technology capable of preventing a drain disturb phenomenon in a nonvolatile memory semiconductor device (column 3, lines 61-64).

Response to Arguments

Applicant's arguments with respect to claims 8,9,17,18,26,27,35 and 36 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

The following patents are cited to further show the state of the art with respect to transistors for integrated circuits:

Hsu et al. (US 6,908,818 B2)

Hwang (5,359,219)

Ishimaru (5,960,272)

Maeda (5,471,082)

Shimizu (US 2002/0113286 A1)

Shone (5,822,243)

Shum et al. (US 2005/0180215 A1)

Terashima et al. (5,874,767).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ida M. Soward whose telephone number is 571-272-

Art Unit: 2822

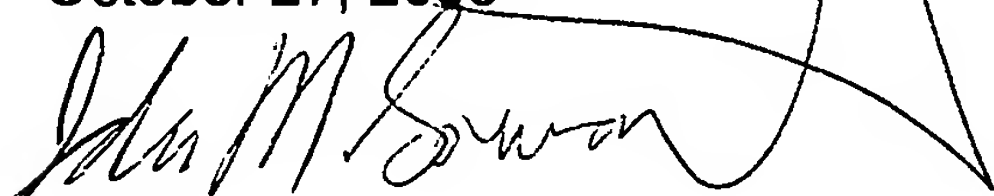
1845. The Examiner can normally be reached on Monday - Thursday 6:30am to 5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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IMS

October 27, 2005



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